

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(Use several sheets if necessary)

Attorney Docket No.:

0502-1021

Application No.:

10/510,112

Applicant:

Vincent GAUD et al.

Filing Date:

October 4, 2004

Group Art Unit:

1714

U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

[illegible]

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

OTHER DOCUMENTS (including patent, etc.)		
		Donya, A.P. et al., "Synthesis of triazenes and azo dyes from aminostyrenes", Zhurnal Vsesoyuznogo Khimicheskogo Obshchestva im. D.I. Mendeleeva (1974), 19(5), 584-6*
		Kamogawa, H. et al., "Syntheses and properties of photochromic polymers of the azobenzene and thiazine series", J. POLYM. SCI., PART A-1 (1968), 6(11), 2967-91
		Lormann, M. et al., "Hydro-dediazoniation of diazonium salts using trichlorosilane: new cleavage conditions for the T ₁ traceless linker," TETRAHEDRON LETTERS (2000), 41(20), 3813-3816

EXAMINER:

DATE CONSIDERED

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* Abstract provided for the Examiner's convenience

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		Nuyken, O. et al., "Laser ablation of arylazo-containing polymers", POLYMER NEWS (1999), 24(8), 257-266
		Nuyken, O. et al., "Synthesis of Polysulfides Containing the Triazeno Group and Their Application as Photoresists in Excimer Laser Polymer Ablation", CHEMISTRY OF MATERIALS (1997), 9(2), 485-494
		Wei, J. et al., "Novel Laser Ablation Resists for Excimer Laser Ablation Lithography. Influence of Photochemical Properties on Ablation", JOURNAL OF PHYSICAL CHEMISTRY B (2001), 105(6), 1267-1275

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